TIME OPTIMAL SETPOINT GENERATOR IN A LITHOGRAPHIC APPARATUS

ABSTRACT

The present invention discloses a lithographic apparatus, a device manufacturing method, and a robotics system capable of specifying a trajectory to be followed by a substrate relative to a radiation beam comprising a position and/or an orientation as a function of time. The specified trajectory is characterized as a mathematical smooth function up to at least the third order which connects a first state and a second state, wherein both the first state and the second state comprise boundary values for at least the position and/or the orientation and for first and second derivatives of the position and/or orientation.